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## In the Claims:

1. (Original) A resist composition comprising one or more basic compounds selected from those represented by the following formula (I):

$$N(X)_n(Y)_{3-n}$$

(I)

wherein, n stands for 1, 2 or 3; side chains Xs are the same or different and each independently represents  $-R^1-O-R^2$  or  $-R^1-C(=O)-O-R^{61}$ , in which  $R^1$ s are the same or different and each independently represents an alkylene group of 1 to 5 carbon atoms,  $R^2$ s are the same or different and each independently represents a linear, branched or cyclic alkyl group of 1 to 20 carbon atoms containing a carbonyl or ester group, and  $R^{61}$ s are the same or different and each independently represents a linear, branched or cyclic alkyl group of 1 to 20 carbon atoms which may contain a carbonyl group, an ester group, an ether group, a hydroxyl group or a lactone ring, or  $R^1$  and  $R^2$ , or  $R^1$  and  $R^{61}$  in the same side chain may be coupled together to form a ring; and side chains Ys are the same or different and each independently represents a hydrogen atom or a linear, branched or cyclic alkyl group of 1 to 20 carbon atoms which may contain an ether or hydroxyl group.

- 2. (Original) A resist composition according to claim 1, wherein n in the formula (I) stands for 1 or 2.
- 3. (Original) A resist composition comprising one or more basic compounds selected from those represented by the following formulas (1) to (4).

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wherein, R<sup>1</sup>s are the same or different and each independently represents a C<sub>1-5</sub> alkylene group, R<sup>2</sup>s are the same or different and each independently represents a linear, branched or cyclic alkyl group of 1 to 20 carbon atoms containing a carbonyl group or an ester group, R<sup>3</sup> represents a hydrogen atom or a linear, branched or cyclic alkyl group of 1 to 20 carbon atoms which may contain a hydroxyl or ether group, and R<sup>4</sup>s are the same or different and each independently represents a linear, branched or cyclic alkyl group of 1 to 20 carbon atoms which may contain a carbonyl, ester or ether group.

4. (Original) A resist composition comprising one or more basic compounds selected from those represented by the following formula (II):

$$\left(\begin{array}{c} R^{63}O \end{array}\right)_{p} N \left(\begin{array}{c} CO_{2}R^{64} \end{array}\right)_{q}$$

$$(II)$$

wherein, R<sup>62</sup> represents a linear or branched alkylene group of 1 to 5 carbon atoms, p stands for 0, 1 or 2 with the proviso that p+q=3, R<sup>63</sup>s are the same or different and each independently represents a hydrogen atom or a linear, branched or cyclic alkyl group of 1 to 15 carbon atoms which may contain an ether, carbonyl, ester or hydroxyl group and R<sup>64</sup>s are the same or different and each independently represents a linear, branched or cyclic alkyl

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group which may contain a carbonyl group, an ester group, an ether group, a hydroxyl group or a lactone ring.

5. (Original) A resist composition comprising one or more basic compounds selected from those represented by the following formula (III):

$$N \left( \begin{array}{c} O \\ O \\ O \end{array} \right)_{3}$$

wherein R<sup>65</sup>s are the same or different and each independently represents a hydrogen atom or a linear, branched or cyclic alkyl group of 1 to 15 carbon atoms which may contain an ether, carbonyl, ester or hydroxyl group.

## 6. (Cancelled)

7. (Original) A resist composition according to claim 2, further comprising an organic solvent, a base resin which is an alkali insoluble or sparingly-soluble resin having an acidic functional group protected with an acid-labile group but becomes alkali soluble upon elimination of said acid-labile group, and an acid generator; and being a positive type.

## 8. (Cancelled)

9. (Original) A resist composition according to claim 4, further comprising an organic solvent, a base resin which is an alkali insoluble or sparingly-soluble resin having an acidic functional group protected with an acid-labile group but becomes alkali soluble upon elimination of said acid-labile group, and an acid generator; and being a positive type.

## 10. (Cancelled)

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11. (Cancelled)

12. (Original) A resist composition according to claim 7, further comprising a dissolution inhibitor.

13. (Cancelled)

14. (Original) A resist composition according to claim 9, further comprising a dissolution inhibitor.

15. (Cancelled)

16. (Cancelled)

17. (Original) A resist composition according to claim 2, further comprising an organic solvent, a base resin which is an alkali soluble resin but becomes sparingly soluble in alkali by crosslinking with a crosslinker, an acid generator and said crosslinker which crosslinks in the presence of an acid; and being a negative type.

18. (Cancelled)

19. (Original) A resist composition according to claim 4, further comprising an organic solvent, a base resin which is an alkali soluble resin but becomes sparingly soluble in alkali by crosslinking with a crosslinker, an acid generator and said crosslinker which crosslinks in the presence of an acid; and being a negative type.

20. (Cancelled)